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Claims

1. (currently amended) A structure for applying photoresist to a surface of a workpiece comprising:
a transfer layer of polydimethylsiloxane with a transferable coating of photoresist on an outer surface of the transfer layer, the transferable coating of photoresist being transferable to the workpiece through physical contact; and
a cushion layer consisting of rubber under the transfer layer, the cushion layer providing flexible support for the transfer layer.
2. (previously presented) The structure of claim 1 further comprising a stiffener layer under the cushion layer.
3. (previously presented) The structure of claim 1 wherein the cushion layer consists of silicone rubber.
- 4-10. cancelled
11. (previously presented) The structure of claim 1 wherein the transfer layer is approximately from 10 to 100 microns thick.
12. (previously presented) The structure of claim 1 wherein the cushion layer is approximately from 0.5 to 3.0 mm thick.
13. cancelled
14. (previously presented) The structure of claim 2 wherein the stiffener layer is approximately 0.1 to 1.0 mm thick.

15. (currently amended) A ~~The~~ structure for applying photoresist to a surface of a workpiece of claim 1 further comprising:

a transfer layer of polydimethylsiloxane with a transferable coating of photoresist on an outer surface of the transfer layer;

a cushion layer consisting of rubber under the transfer layer, the cushion layer providing flexible support for the transfer layer; and

a cover-tape attached to the cushion layer opposite to the layer of photoresist, the cover-tape being larger in area than the cushion layer and extending beyond at least first and second edges of the cushion layer.

16. (currently amended) A ~~The~~ structure for applying photoresist to a surface of a workpiece of claim 1 further comprising:

a transfer layer of polydimethylsiloxane with a transferable coating of photoresist on an outer surface of the transfer layer;

a cushion layer consisting of rubber under the transfer layer, the cushion layer providing flexible support for the transfer layer; and

a stiffener layer attached to the cushion layer, and a cover-tape attached to the stiffener layer opposite to the layer of photoresist.

17. (previously presented) A structure for applying photoresist to a surface of a workpiece comprising:

a cover-tape; and

at least two photoresist transfer pads attached to the cover-tape, the photoresist transfer pads comprising a polymer layer with a transferable coating of photoresist on an outer surface of the polymer layer, and a cushion layer under the polymer layer opposite the transferable coating of photoresist.

18. (previously presented) The structure of claim 17 wherein the polymer layer consists of polydimethylsiloxane.

19. (previously presented) The structure of claim 17 wherein the photoresist transfer pads further comprise a stiffener layer attached to the cushion layer.

20. (previously presented) The structure of claim 17 wherein the photoresist transfer pads further comprise a stiffener layer attached to the cushion layer, the polymer layer consists of polydimethylsiloxane and the cushion layer consists of silicone rubber.

21. (previously presented) The pad of claim 17 wherein the cushion layer consists of silicone rubber.

22. (previously presented) The structure of claim 17 wherein the cover-tape and photoresist pads are formed into a roll.

23. (previously presented) The structure of claim 22 wherein the photoresist pads are sequentially disposed on the cover-tape so that unrolling the roll sequentially exposes the photoresist pads.